

**ROCHESTER INSTITUTE OF TECHNOLOGY
MICROELECTRONIC ENGINEERING**

ETM MASK

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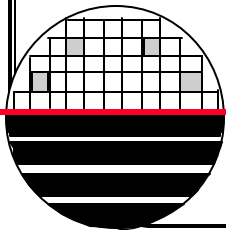
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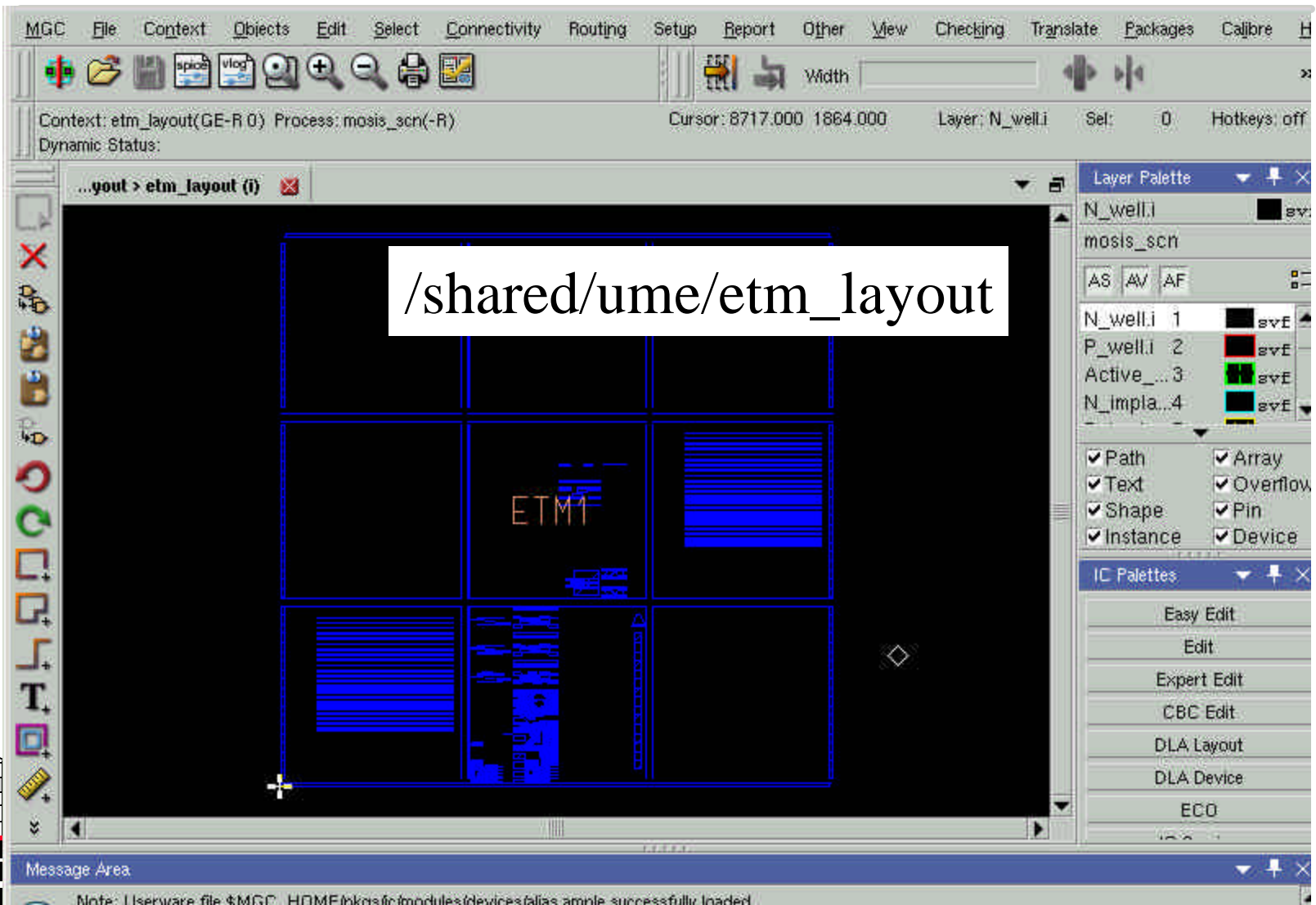


INTRODUCTION

This mask was created by Brian Bennamati in 1987 as part of his MS thesis. It has been used at Eastman Kodak and at RIT ever since. This document shows the details of this mask.



LOCATION ON VLSI COMPUTERS



EXPOSURE TEST MASK ETM-1

Top three cells are blank

Cell A – Vertical
Lines/Spaces/Holes/Islands

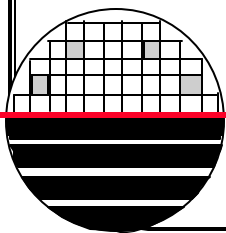
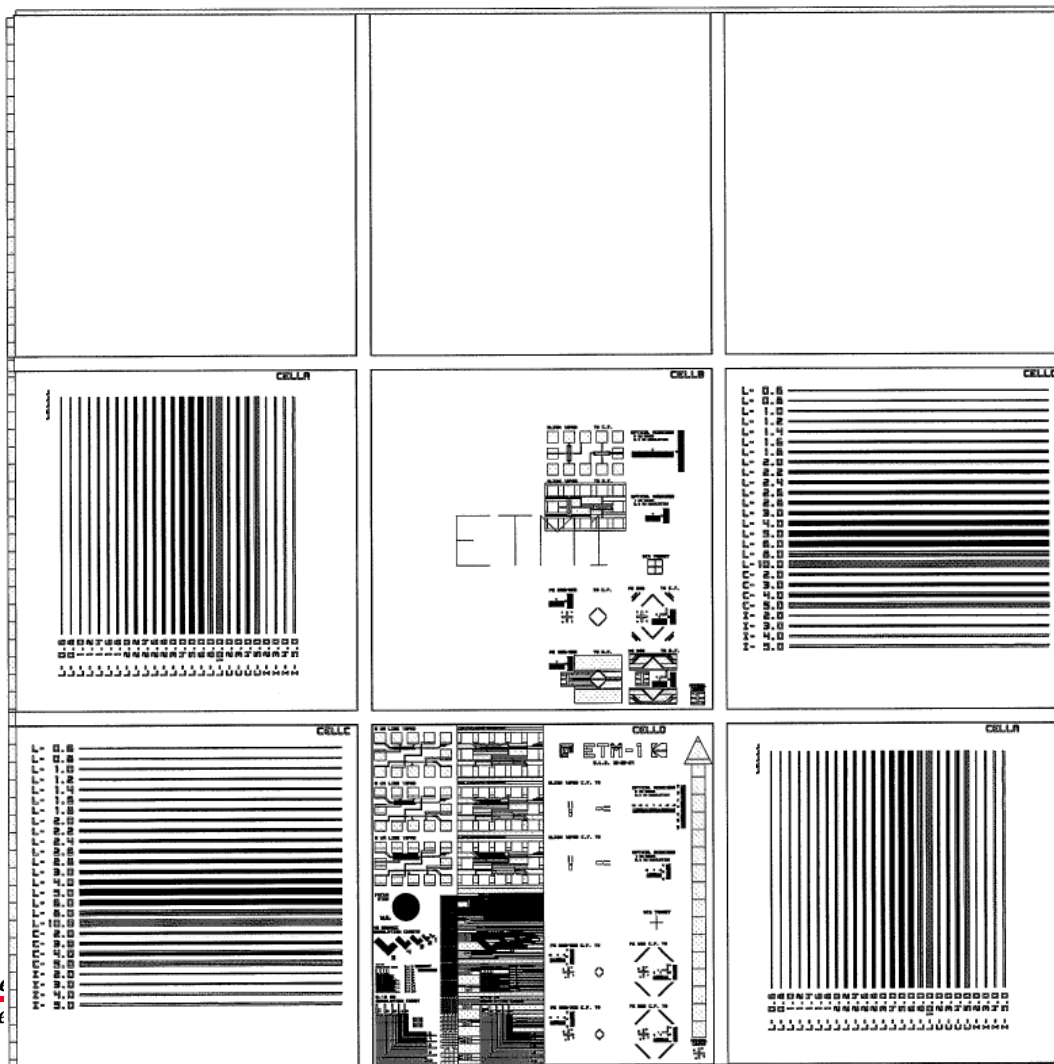
Cell B – 1st Layer for Overlay
Evaluation

Cell C – Horizontal
Lines/Spaces/Holes/Islands

Cell D – Image Evaluation
Lines/Spaces/Checker Boards/
Focus Star/Murray Dagger/
2nd Layer for Overlay Evaluation

Cell A	Cell B	Cell C
Cell C	Cell D	Cell A

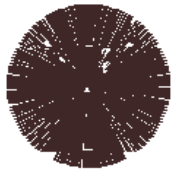
ENTIRE ETM MASK



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CELL D

FOCUS
STAR



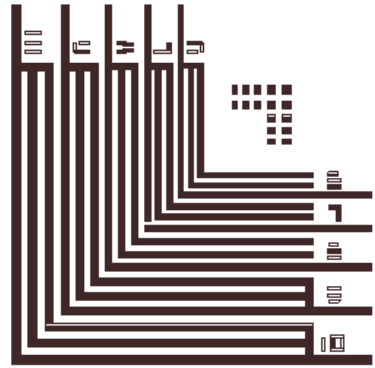
5 DEGREE
RESOLUTION C-PARTS



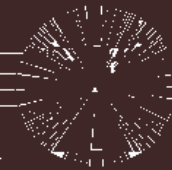
MURRAY
COCKERS



5-10 UM
RESOLUTION C-PART



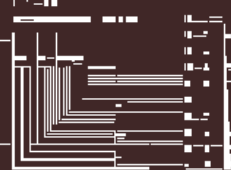
FOCUS
STAR



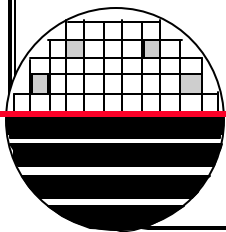
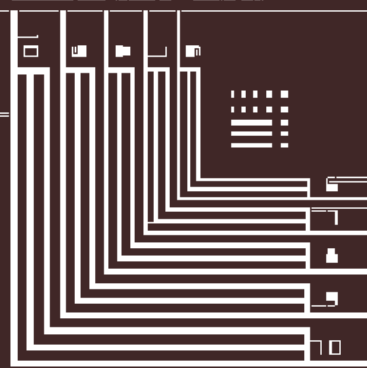
45 DEGREE
RESOLUTION CHICKS



MURRAY
COCKERS

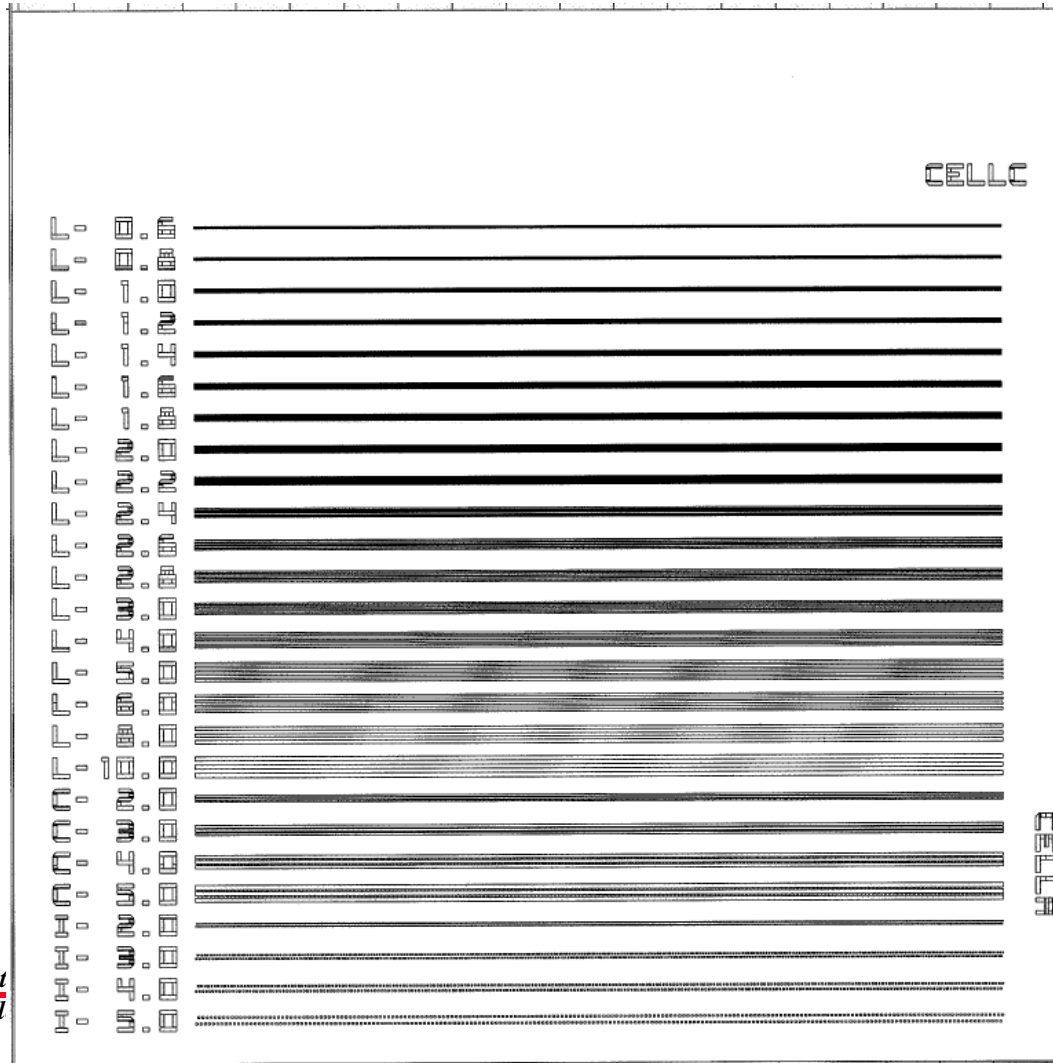


5-10 UM
RESOLUTION CHICKS



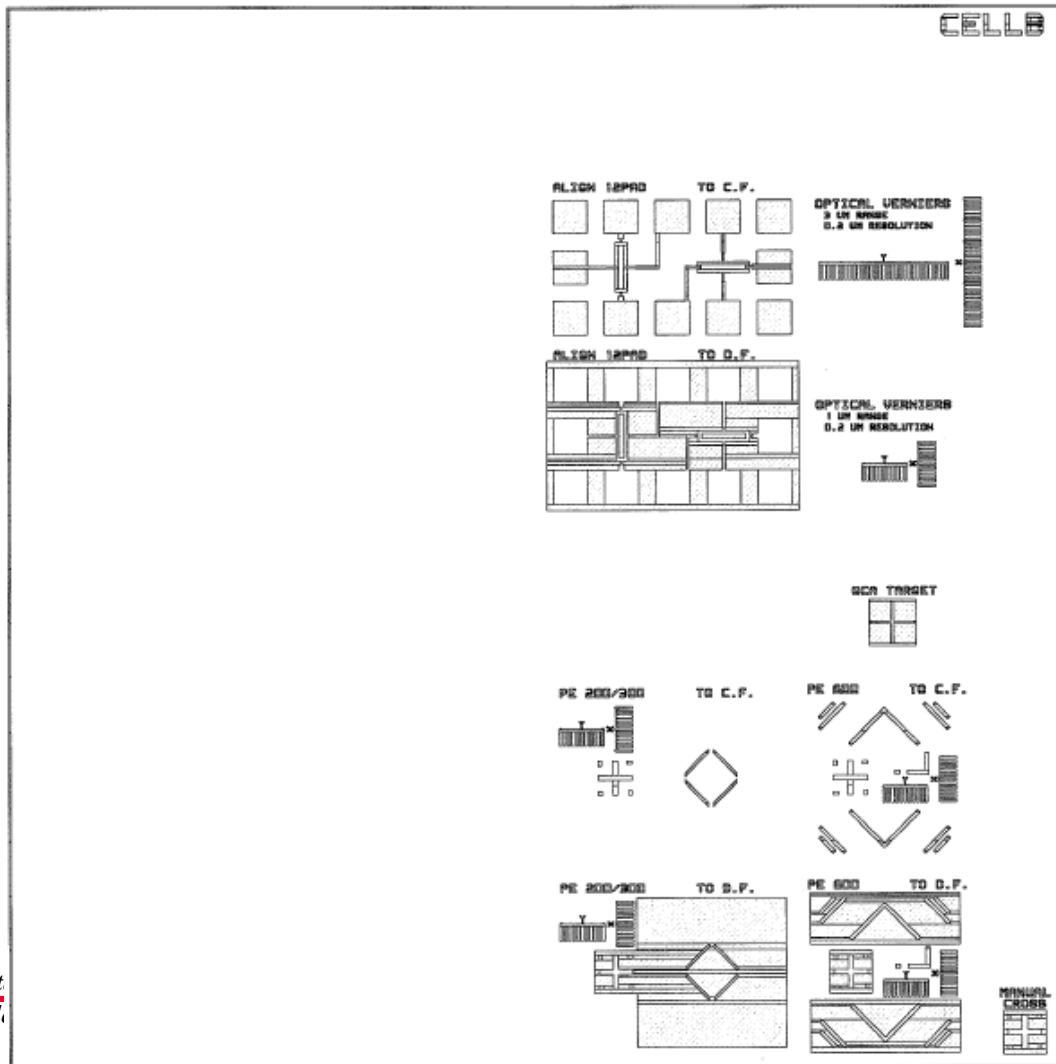
R
A

CELL A AND C



Rochest
Microel

CELL B



Rochest
Microel

Jake Leveto Google map of the ETM Mask

<http://nuclearnova.com/microe/etm.html>

